

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	49	("205"/\$.ccls. "204"/\$.ccls.) and (electrolysis electrolytic electrochemic\$4 electrodeposit\$5 electroplat\$5) and anodic near5 dissolution and (surfactant wetting carrier suppressor suppresser) and (brighten\$4 accelerator)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/14 15:40
L2	34	L1 and wafer	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/14 15:38
L3	48	L1 and rate	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/14 15:38
L4	34	L1 and wafer and rate	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/14 15:40
L5	1	L1 and wafer and rate near5 electropolish\$3	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/14 15:40
L6	6	("205"/\$.ccls. "204"/\$.ccls.) and (electrolysis electrolytic electrochemic\$4 electrodeposit\$5 electroplat\$5) and wafer and rate near5 electropolish\$3 and (surfactant wetting carrier suppressor suppresser) and (brighten\$4 accelerator)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/14 15:53
L7	36	("205"/\$.ccls. "204"/\$.ccls.) and (electrolysis electrolytic electrochemic\$4 electrodeposit\$5 electroplat\$5) near5 rate and electropolish\$3 and (surfactant wetting carrier suppressor suppresser) and (brighten\$4 accelerator)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/14 15:47

L8	6	(electrolysis electrolytic electrochemic\$4 electrodeposit\$5 electroplat\$5) and wafer and rate near\$5 electropolish\$3 and (surfactant wetting carrier suppressor suppresser) and (brighten\$4 accelerator)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/14 15:53
S2	108	("205"/\$.ccls. "204"/\$.ccls.) and (electrolysis electrolytic electrochemic\$4 electrodeposit\$5 electroplat\$5) and electropolish\$3 and (surfactant wetting carrier suppressor suppresser) and (brighten\$4 accelerator)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/13 12:44
S3	58	("205"/\$.ccls. "204"/\$.ccls.) and (electrolysis electrolytic electrochemic\$4 electrodeposit\$5 electroplat\$5) and electropolish\$3 and (surfactant wetting carrier suppressor suppresser) and (brighten\$4 accelerator) and leveler	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/09 17:40
S4	118	("205"/\$.ccls. "204"/\$.ccls.) and (electrolysis electrolytic electrochemic\$4 electrodeposit\$5 electroplat\$5) and anodic and (surfactant wetting carrier suppressor suppresser) and (brighten\$4 accelerator) and leveler	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/09 17:41
S5	27	("205"/\$.ccls. "204"/\$.ccls.) and (electrolysis electrolytic electrochemic\$4 electrodeposit\$5 electroplat\$5) and anodic near\$5 dissolution and (surfactant wetting carrier suppressor suppresser) and (brighten\$4 accelerator) and leveler	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/09 17:48
S6	49	("205"/\$.ccls. "204"/\$.ccls.) and (electrolysis electrolytic electrochemic\$4 electrodeposit\$5 electroplat\$5) and anodic near\$5 dissolution and (surfactant wetting carrier suppressor suppresser) and (brighten\$4 accelerator)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/14 14:53
S7	22	("205"/\$.ccls. "204"/\$.ccls.) and (electrolysis electrolytic electrochemic\$4 electrodeposit\$5 electroplat\$5) and anodic near\$5 dissolution and (surfactant wetting carrier suppressor suppresser) and (brighten\$4 accelerator) not S5	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/09 17:50

S8	10	("205"/\$.ccls. "204"/\$.ccls.) and (electrolysis electrolytic electrochemic\$4 electrodeposit\$5 electroplat\$5) and electrodisolution and (surfactant wetting carrier suppressor suppresser) and (brighten\$4 accelerator)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/09 17:51
S9	905	("205"/\$.ccls. "204"/\$.ccls.) and (electrolysis electrolytic electrochemic\$4 electrodeposit\$5 electroplat\$5) and electropolish\$3	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/13 11:31
S10	611	("205"/\$.ccls. "204"/\$.ccls.) and (electrolysis electrolytic electrochemic\$4 electrodeposit\$5 electroplat\$5) and electropolish\$3 and (trench microvia recess\$3 "through-hole" "thru-hole" opening hole via)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/13 12:45
S11	464	("205"/\$.ccls. "204"/\$.ccls.) and (electrolysis electrolytic electrochemic\$4 electrodeposit\$5 electroplat\$5) and electropolish\$3 and (trench microvia recess\$3 "through-hole" "thru-hole" opening hole via) and copper	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/13 12:45
S12	99	("205"/\$.ccls. "204"/\$.ccls.) and (electrolysis electrolytic electrochemic\$4 electrodeposit\$5 electroplat\$5) and electropolish\$3 and (trench microvia recess\$3 "through-hole" "thru-hole" opening hole via) and copper and (((zero off pause) near5 (current)) ((off relaxation rest) near5 time) ((off relaxation) near5 period) (zero near5 pulse))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/13 12:46